

IN THE CLAIMS

Please amend the claims as follows:

Claim 1 (Currently Amended): A wafer processing apparatus comprising:

a chamber;

a first opening portion through which the interior and the exterior of the chamber communicate; and

a door that substantially closes the first opening portion,

wherein the door has a projection which partially protrudes from the outer shape of the door, and when the door is positioned to substantially close the first opening portion only the projection contacts with a peripheral portion of the first opening portion, the projection provides a predetermined positional relationship between the door and the first opening by contacting with a peripheral portion of the first opening, when the door substantially closes the first opening.

Claim 2 (Original): A wafer processing apparatus according to claim 1, wherein the projection is provided at one of four corners of the door so as to protrude toward the outside of the door.

Claim 3 (Original): A wafer processing apparatus according to claim 1, wherein in case that the door is positioned to substantially close the first opening portion, an aperture through which the interior and the exterior of the chamber are in communication with each other exists.

Claim 4 (Currently Amended): A wafer processing apparatus including a mini-environment portion having a chamber therein and used for transferring a wafer between a clean box having a lid and housing the wafer and the chamber, said apparatus comprising:

a first opening portion in communication with the chamber, facing to an opening of the clean box so as to allow loading and unloading the wafer between the clean box and the mini-environment portion; and

a door that closes, when the transfer of the wafer is not performed, the first opening portion and opens, when the transfer of the wafer is performed,

wherein the door has a projection which partially protrudes from the outer shape of the door, and when the door is positioned to close the first opening portion only the projection contacts with periphery portion of the first opening portion, the projection provides a predetermined positional relationship between the door and the first opening by contacting with a peripheral portion of the first opening, when the door substantially closes the first opening.

Claim 5 (Original): A wafer processing apparatus according to claim 4, wherein the projection is provided at one of four corners of the door so as to protrude toward the outside of the door.

Claim 6 (Currently Amended): A wafer processing apparatus according to claim 4, wherein in case that the door is positioned to substantially close the first opening portion, an aperture through which the interior and the exterior of the chamber are in communication with each other exists.

Claim 7 (Currently Amended): A wafer processing apparatus comprising:

a chamber;

a first opening portion through which the interior and the exterior of the chamber communicate; and

a door that substantially closes the first opening portion,

wherein the door has a projection which is made into a shape so as to suppress an influence on air flow passing through a communication path from the interior to the exterior of the chamber when comparing a case that there is no projection, and when the door is positioned to substantially close the first opening portion only the projection contacts with periphery portion of the first opening portion, the projection provides a predetermined positional relationship between the door and the first opening by contacting with a peripheral portion of the first opening, when the door substantially closes the first opening.

Claim 8 (Currently Amended): A wafer processing apparatus, comprising:

a chamber having a wall portion with a window opening through which wafers are received into the chamber or remove therefrom; and

a door configured to close the window opening, the door comprising a plurality of ~~protrusions~~ projections extending from an outermost perimeter thereof, the plurality of ~~protrusions~~ projections being shaped to reduce gas flow turbulence generated by opening and closing the door, wherein, when the door is positioned to substantially close the window opening, only the plurality of ~~projections~~ projections ~~contact~~ contact a surface of the wall portion adjacent to the window opening, the projection provides a predetermined positional relationship between the door and the first opening by contacting with a peripheral portion of the first opening, when the door substantially closes the first opening.

Claim 9 (Currently Amended): A wafer processing apparatus according to claim 8, wherein each of the ~~projection of the plurality~~ plurality of projections is provided at a corner region of the door.

Claim 10 (Previously Presented): A wafer processing apparatus according to claim 8, wherein, when the door is positioned to substantially close the window opening, an aperture through which an interior and an exterior of the chamber are in communication with each other exists.